Investigation of BaSi₂ homojunction solar cells on a p⁺-BaSi₂/p⁺-Si tunnel junction towards BaSi₂/Si tandem solar cells

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Abstract

Towards a BaSi₂-pn/Si-pn tandem solar cell, a p^+ -BaSi₂/ p^+ -Si tunnel junction (TJ) with a low resistance of 0.081 Ω cm² is achieved by molecular beam epitaxy and a conversion efficiency of a 500-nm-thick BaSi₂ homojunction solar cell on TJ is simulated by automat for simulation of heterostructures (AFORS-HET). Large photoresponsivities experimentally obtained for BaSi₂ films formed on TJ indicates great potential for a BaSi₂-pn/Si-pn tandem solar cell.

1. Introduction

It is important for solar cell materials to have a large absorption coefficient (α), and a suitable band gap (ca. 1.4 eV) which matches the solar spectrum to achieve a high conversion efficiency (η) . Materials composed of earth abundant and environmental friendly elements are also desirable. Si-based solar cells occupy more than 90% of the photovoltaic market. However, the band gap of crystalline Si (c-Si) is 1.1eV, which is 0.3 eV smaller than the ideal band gap considered suitable for solar cell applications [1]. We have focused much attention on semiconducting BaSi₂ because BaSi₂ is a material of choice for targeting $\eta > 30\%$ in a Si-based tandem structure solar cell. The band gap of BaSi₂ is 1.3 eV, which matches the solar spectrum much better than c-Si[2], and can be increased by adding Sr, O, or C atoms [3-5]. Moreover, it has a very large α of 3×10^4 cm⁻¹ at 1.5 eV and can be epitaxially grown both on Si(111) and Si(001)[6]. An η of over 25% can be expected for a 2 µm-thick BaSi₂ pn homojunction solar cell[7]. In our previous work, we grew boron (B)-doped p-BaSi₂ with a hole concentration (p) at 10^{18} cm⁻³ as an emitter layer on a flat n-Si(111) substrate and a textured n-Si(001) substrate with a pyramid structure consisting of {111} facets to form p-BaSi₂/n-Si heterojunction solar cells and achieved an η of 9.9 and 4.6%, respectively [8-9].

In this study, prior to the formation of a BaSi₂-pn/Si-pn tandem solar cell, we aimed to form a p⁺-BaSi₂/p⁺-Si tunnel junction (TJ), which is necessary to make the electrical contact between BaSi₂-pn and Si-pn solar cells sufficiently small. We also simulated the η of a BaSi₂ homojunction solar cells on TJ, using automat for simulation of heterostructures (AFORS-HET)[10]. An η of 16.5% was simulated in a 500-nm-thick BaSi₂ homojunction solar cell with an open-circuit voltage (V_{OC}) of 0.76 V, a short-circuit density (J_{SC}) of 25.8 mA/cm² and a fill factor (*FF*) of 83.9%. The TJ

properties were confirmed by experiment, and the tunnel current density reached 18.3 A/cm² at a bias voltage of 1.0 V, showing great potential for $BaSi_2$ homojunction solar cells on a TJ.

2. Experiment

The solar cell characteristics and key parameters such as band alignment, the current density versus voltage (J-V) characteristics and suitable thickness of each layer were determined using the AFORS-HET (v2.5) simulation.

For experiment, an ion-pumped molecular beam epitaxy (MBE) system with a base pressure of less than 10⁻⁸ Pa, equipped with an electron-beam evaporation source for Si as well as standard Knudsen cells for Ba, Sb and B was used. To make a p^+ -BaSi₂/ p^+ -Si TJ, we set their p values to exceed the effective density of states in the valence band for BaSi₂ $(2.0 \times 10^{19} \text{ cm}^{-3})$ and Si $(2.69 \times 10^{19} \text{ cm}^{-3})$. The procedure of the sample preparation is as follows. Si and B were co-deposited at a substrate temperature (T_S) of 500 °C to form a 40 nm-thick p⁺-Si epitaxial layer ($p = 4.3 \times 10^{19} \text{ cm}^{-3}$) after thermal cleaning of the substrate. Afterwards, Ba was deposited at $T_{\rm S} = 500$ °C to form a 1 nm-thick BaSi₂ epitaxial template by reactive deposition epitaxy. This template works as a kind of seed crystal for subsequent layer. B, Ba and Si were co-deposited on the template at $T_{\rm S} = 650$ °C by MBE to form a 10 nm-thick p^+ -BaSi₂ epitaxial film with p = 2×10^{19} cm⁻³ on the p⁺-Si layer on a p-Si(001) substrate with resistivity (ρ) of 2–5 Ω cm (sample A) and $\rho = 0.07 \Omega$ cm (sample B) with a structure of p⁺-BaSi₂/p⁺-Si TJ. Subsequently, for sample C, T_S was decreased to 600 °C to fabricate a 500 nm-thick p-BaSi₂ film with $p = 1 \times 10^{17}$ cm⁻³. After that, a 10 nm-thick n-BaSi₂ epitaxial film with $n = 2 \times$ 10¹⁹ cm⁻³ and a 3 nm-thick a-Si were grow. TJ properties of samples A and B were checked by J-V characteristics with 150 nm-thick sputtered Al electrodes with a diameter of 1 mm on the front side and full on the back side. The photoresponse spectra were measured using a xenon lamp with a 25-cm-focal-length single monochromator (Bunko Keiki, SM-1700A and RU-60N). All measurements were performed at room temperature.

3. Results and discussions

Figure 1 show the schematic diagram and the band alignment of a n-BaSi₂(10 nm, $n = 2 \times 10^{19}$ cm⁻³)/p-BaSi₂(500 nm, $p = 1 \times 10^{17}$ cm⁻³)/p⁺-BaSi₂(10 nm, $p = 2 \times 10^{19}$ cm⁻³)/p⁺-Si (40 nm, $p = 4.3 \times 10^{19}$ cm⁻³)/p-Si(500

 μ m, $\rho = 0.07 \ \Omega$ cm) solar cell. From Fig. 1(b), the electron-hole pairs generate in the absorber p-BaSi₂ region, afterwards, electrons transport toward the n-BaSi₂ side by the build-in electric field and holes transport to the p-Si side across the p⁺-BaSi₂/ p⁺-Si TJ, leading to the operation of the solar cell.



Fig. 1 (a) Schematic diagram and (b) band alignment of a $BaSi_2$ homojunction solar cell on a p^+ - $BaSi_2/p^+$ -Si TJ.

Figure 2 shows the simulated *J-V* characteristics of the solar cell in the dark and under standard AM1.5 illumination. Good rectifying properties were achieved and an η of 16.5% was obtained with a $V_{\rm OC}$ of 0.76 V, a $J_{\rm SC}$ of 25.8 mA/cm² and a *FF* of 83.9%.



Fig. 2 *J-V* characteristics of the solar cell in the dark and under standard AM1.5 illumination.



Fig. 3 J-V characteristics of samples A and B.

Figure 3 shows the *J*-V characteristics of samples A and B. Bias voltages were applied to the p^+ -BaSi₂ layer with respect to the bottom p-Si substrate. The nearly linear behavior of sample B, which was grown on a p-Si(001) substrate with $\rho = 0.07 \ \Omega$ cm, indicates that the sample works like a constant resistance under the bias voltage. Even under

a very small bias voltage, the carriers could still tunnel through the p⁺-BaSi₂/ p⁺-Si TJ without being blocked. And the tunnel current density reached 18.3 A/cm² at a bias voltage of 1.0 V. Sufficiently small TJ resistance of 0.081 Ω cm² was achieved. In contrast, the sample grown on a medium resistive p-Si substrate showed high resistance especially around 0 V, which will block the transport of carriers.

Figure 4 shows the photoresponse properties of sample C under various forward and reverse bias voltages V_{bias} . The direction of the current flow changed between the reverse and forward bias conditions, as expected. Light absorption produces electron-hole pairs that are separated by the electric field between the electrodes, which leads to current flow in the external circuit as the photoexcited carriers drift before recombination. Photocurrents were increased at around 1000 nm, corresponding to the absorption edge of BaSi₂. The photoresponsivity reached 0.35 A/W at 850 nm at V_{bias} =1V, corresponding to an external quantum efficiency (EQE) of 54%. Next, we plan to form BaSi₂ homojunction solar cells on the TJ using the p-Si(001) substrate with $\rho = 0.07 \,\Omega$ cm.



Fig. 4 Photoresponse properties of sample C under bias voltages.

3. Conclusions

A BaSi₂ homojunction solar cell on a p⁺-BaSi₂/p⁺-Si tunnel junction was simulated by AFORS-HET, and an efficiency of 16.5% was obtained. The tunnel properties of the p⁺-BaSi₂/p⁺-Si junction were confirmed, and the tunnel current density reached 18.3 A/cm² at a bias voltage of 1.0 V. Large photoresponsivity reaching 0.35 A/W at 850 nm at V_{bias} =1V, which corresponds to EQE = 54% show great promise of BaSi₂ on TJ for use in Si-based tandem solar cells.

Acknowledgements

This work was financially supported by JSPS KAKENHI Grant Numbers 15H02237 and 17K18865, and JST MIRAI.

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